

ABSTRACT

SILICON-CONTAINING COMPOSITION FOR FINE PATTERN FORMATION AND METHOD FOR FINE PATTERN FORMATION USING THE SAME

The present invention provides a composition for forming a fine pattern with high dry etching resistance and a method for forming the fine pattern. The composition for fine pattern formation containing: a resin containing a repeating unit having a silazane bond; and a solvent as well as a method for fine pattern formation using the same.

Fig 1